AUG 2 0 2003 & Ocket No.: 49657-947

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of : **RESPONSE UNDER 37 CFR 1.116** 

**EXPEDITED PROCEDURE** 

**PATENT** 

Yoshikazu NAGAMURA, et al. : Customer Number: 20277

Confirmation Number: 6590

Serial No.: 09/779,839 : Group Art Unit: 1746

Filed: February 09, 2001 : Examiner: M. Kornakov

For: METHOD OF AND APPARATUS FOR WASHING PHOTOMASK AND WASHING

SOLUTION FOR PHOTOMASK

## **RESPONSE AFTER FINAL**

Mail Stop AF Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

The following remarks are submitted in response to the Final Office Action dated May 20, 2003.

## REMARKS

Claims 1-7 and 15 are pending.

## THE DOUBLE PATENTING REJECTION

Claims 1-7 and 15 were rejected on the grounds of obviousness-type double patenting over claims 10 and 11 of U.S. Patent No. 6,277,205.

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